

A)Amendments to the Claims:

Claim 1. (currently amended) A vacuum evaporation deposition method of the winding type in which, under ~~the~~an atmosphere of reduced pressure, an insulating material base film is continuously fed out, cooled in close contact with a cooling roller and metal is evaporated onto said insulating material base film to deposit a metal film thereon, the method characterized in that before the deposition of the metal film, said insulating material base film is closely contacted with said cooling roller by charging said insulating material base film, and after the deposition of the metal film, said insulating material base film is closely contacted with said cooling roller by applying a voltage between said metal film and said cooling roller.

Claim 2 . (currently amended) A vacuum evaporation deposition method of the winding type according to claim 1, in which in the step of charging said insulating material base film[,] is performed with charged particles ~~are~~ irradiated onto the running insulating material base film[,] while being scanned in the width direction of said insulating material base film.

Claim 3. (currently amended) A vacuum evaporation deposition method of the winding type according to claim 2, in which said charged particles are irradiated[,] at ~~the~~a time when said insulating material base film ~~has~~is contacted with said cooling roller.

Claim 4. (currently amended) A vacuum evaporation deposition method of the winding type according to claim 1, in which in the step of applying the voltage

between the metal film and said cooling roller, a DC voltage is applied between an auxiliary roller for guiding said insulating material base film with said metal film deposited[,] thereon and said cooling roller.

Claim 5. (currently amended) A vacuum evaporation deposition method of the winding type according to claim 4, in which the step of applying the voltage between the metal film and said cooling roller includes a step of measuring a surface potential of said metal film and another step of so controlling the applying voltage as to ~~put~~ place said surface potential within a predetermined range.

Claim 6. (currently amended) A vacuum evaporation deposition method of the winding type according to claim 1, in which a mask pattern for defining a deposition region of the metal film is formed on the surface ~~to be deposited~~, of the insulating material base film before the step of charging the insulating material base film.

Claim 7. (currently amended) A vacuum evaporation deposition method of the winding type according to claim 1, in which electricity ~~of-on~~ said insulating material base film ~~are-is~~ removed after the deposition of the metal film.

Claim 8. (currently amended) A vacuum evaporation deposition apparatus of the winding type in which there are provided in a vacuum chamber, an unwinding roller for continuously feeding an insulating material base film, a winding roller for taking up said insulating material base film, a cooling roller for cooling said insulating material base film when in contact, said rollers arranged between said unwinding roller[,] and said winding roller, and an evaporation source for depositing a metal film

on said insulating material base film[,] arranged ~~in face~~ facing to said cooling roller, characterized in that said apparatus ~~comprises~~ includes, charged-particles irradiating means for irradiating charged particles onto said insulating material base film, said irradiating means arranged between said unwinding roller and said evaporation source, an auxiliary roller for guiding said insulating material base film in contact with the deposited metal film, said auxiliary roller arranged between said winding roller and said cooling roller, and voltage-applying means for applying a DC voltage between said auxiliary roller and said cooling roller.

Claim 9. (currently amended) A vacuum evaporation deposition apparatus of the winding type according to claim 8, in which there is provided detecting means for detecting a surface potential of said metal film deposited on said insulating material base film, said detecting means arranged between said cooling roller and said auxiliary roller, and controlling means for controlling the applying voltage of said voltage supplying means on the basis of the detected output of said detecting means.

Claim 10. (currently amended) A vacuum evaporation deposition apparatus of the winding type according to claim 8, in which said charged-particles irradiating means is arranged ~~in face~~ facing to the peripheral surface ~~on~~ of said cooling roller.

Claim 11. (currently amended) A vacuum evaporation deposition apparatus of the winding type according to claim 8, in which mask-pattern forming means is arranged between said unwinding roller and said charged-particles irradiating means[,] for defining a mask pattern of ~~the~~ deposition regions of said metal film on said insulating material base film.

Claim 12. (currently amended) A vacuum evaporation deposition apparatus of the winding type according to claim 8, in which electricity removal means is arranged between said auxiliary roller and said winding roller for removing electricity ~~of~~on said insulating material base film.